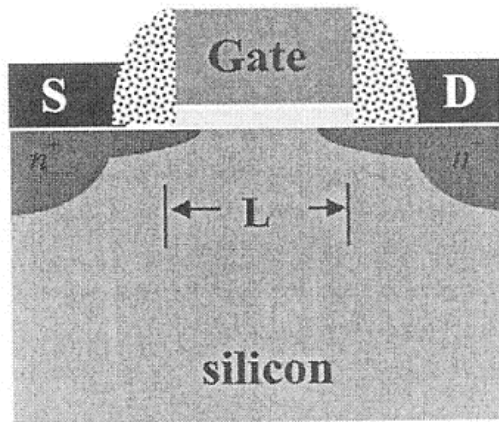


Ballistic Transport in FETs with/without scattering

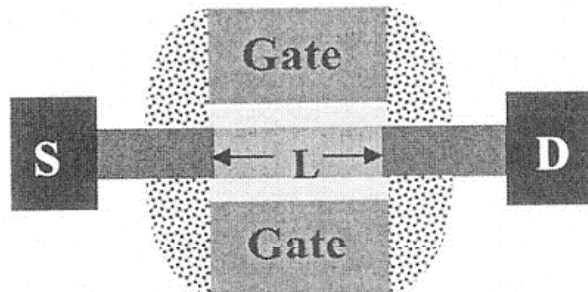
Yu Cao

Nov 24, 2009

Nano-scale MOSFET Structure

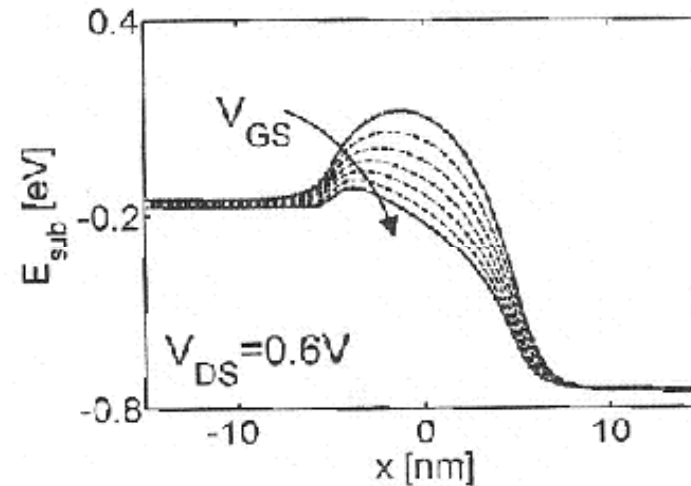
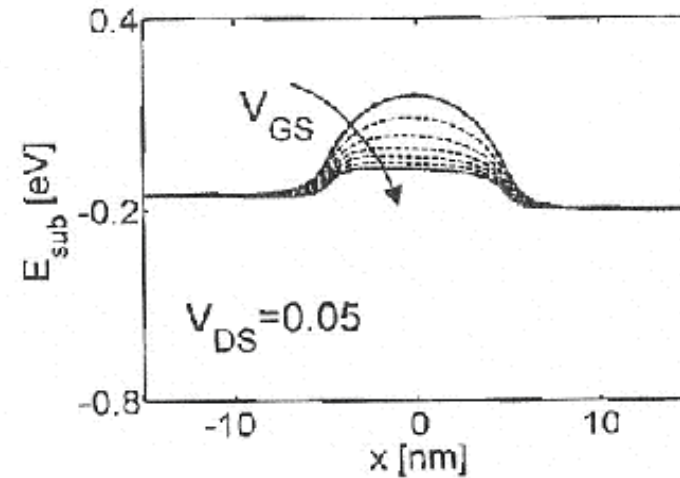


(a)

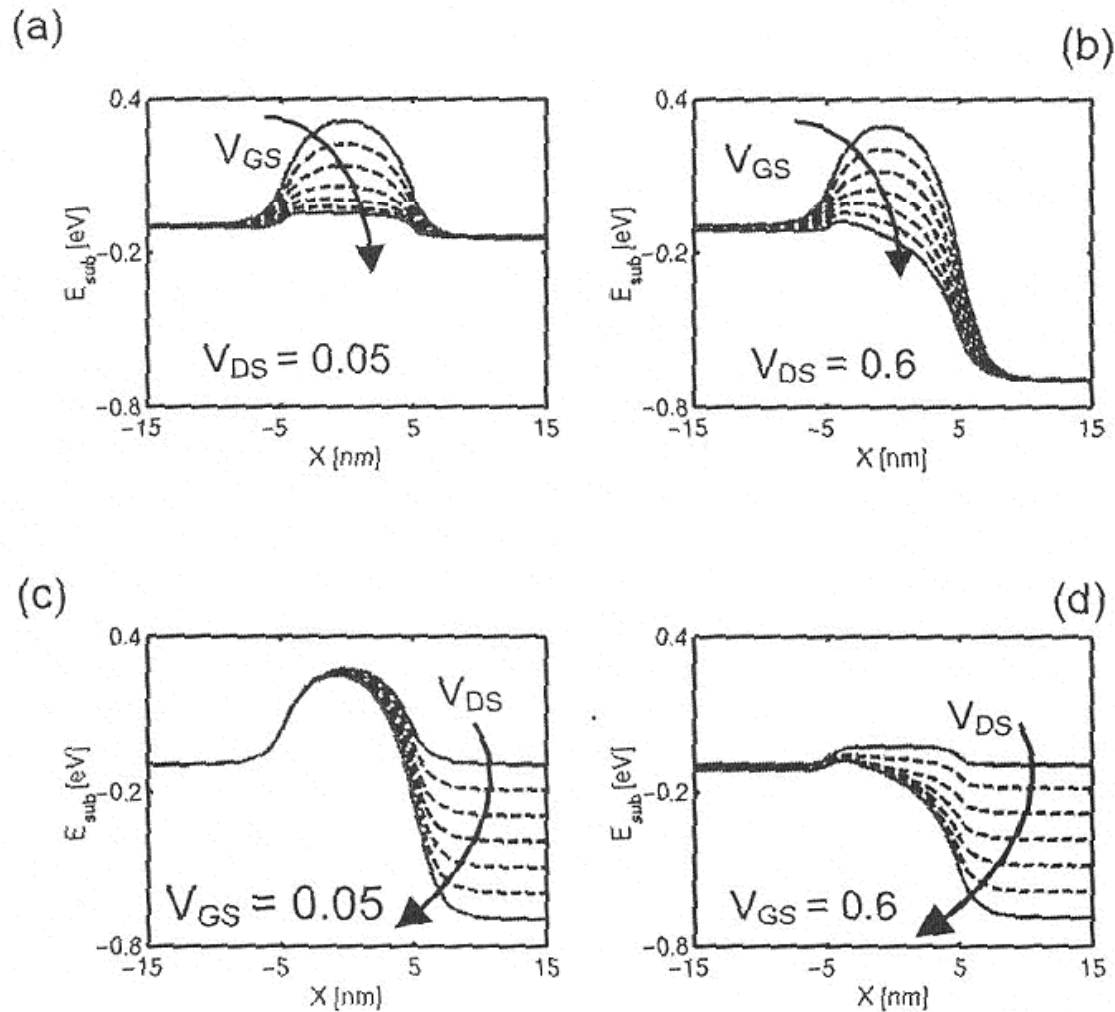


(b)

Cross sectional sketches of: a) a bulk, silicon MOSFET and b) a double-gate MOSFET. The third dimension, the width, W , of the MOSFET, is into the page.



Barrier Controlled by Gate and Drain



Electron Distribution and Velocity in Channel

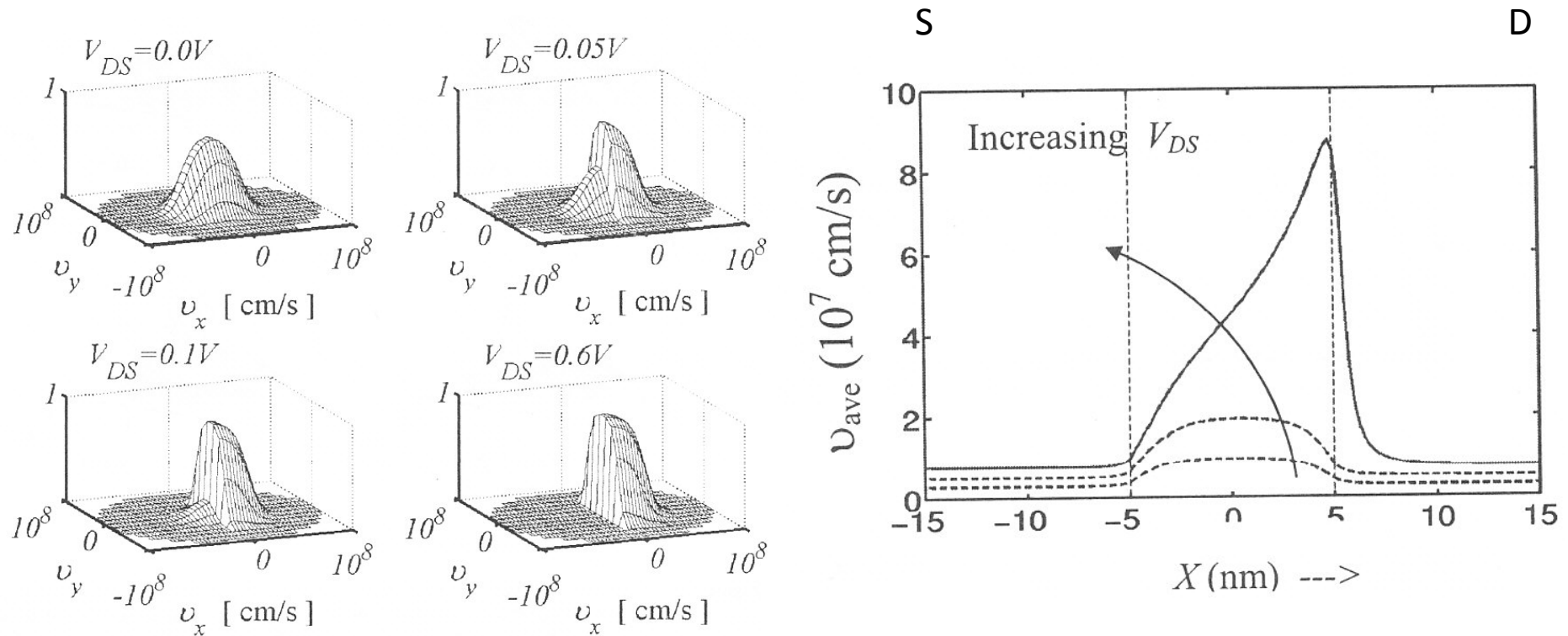


Figure 3.5. Electron distribution function at the top of the source-channel barrier for a ballistic n-MOSFET as computed under high gate and four different drain biases. (Reproduced with permission from [3.9])

Average velocity vs position for the ballistic, double-gate MOSFET

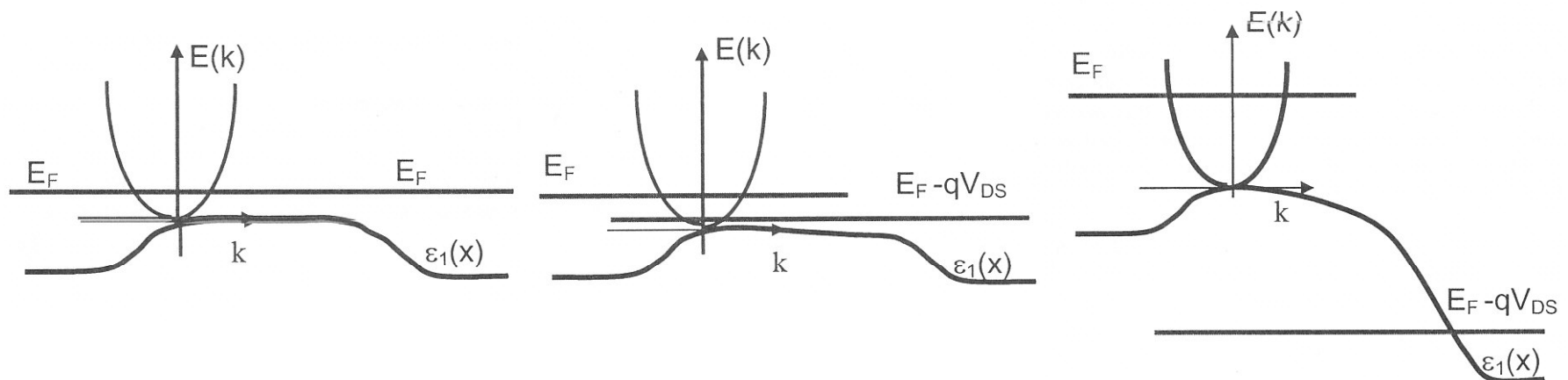
Natori's Ballistic MOSFET Model

- Above threshold, the total carrier density is approx. independent of V_{DS}

- Equation for Fermi level

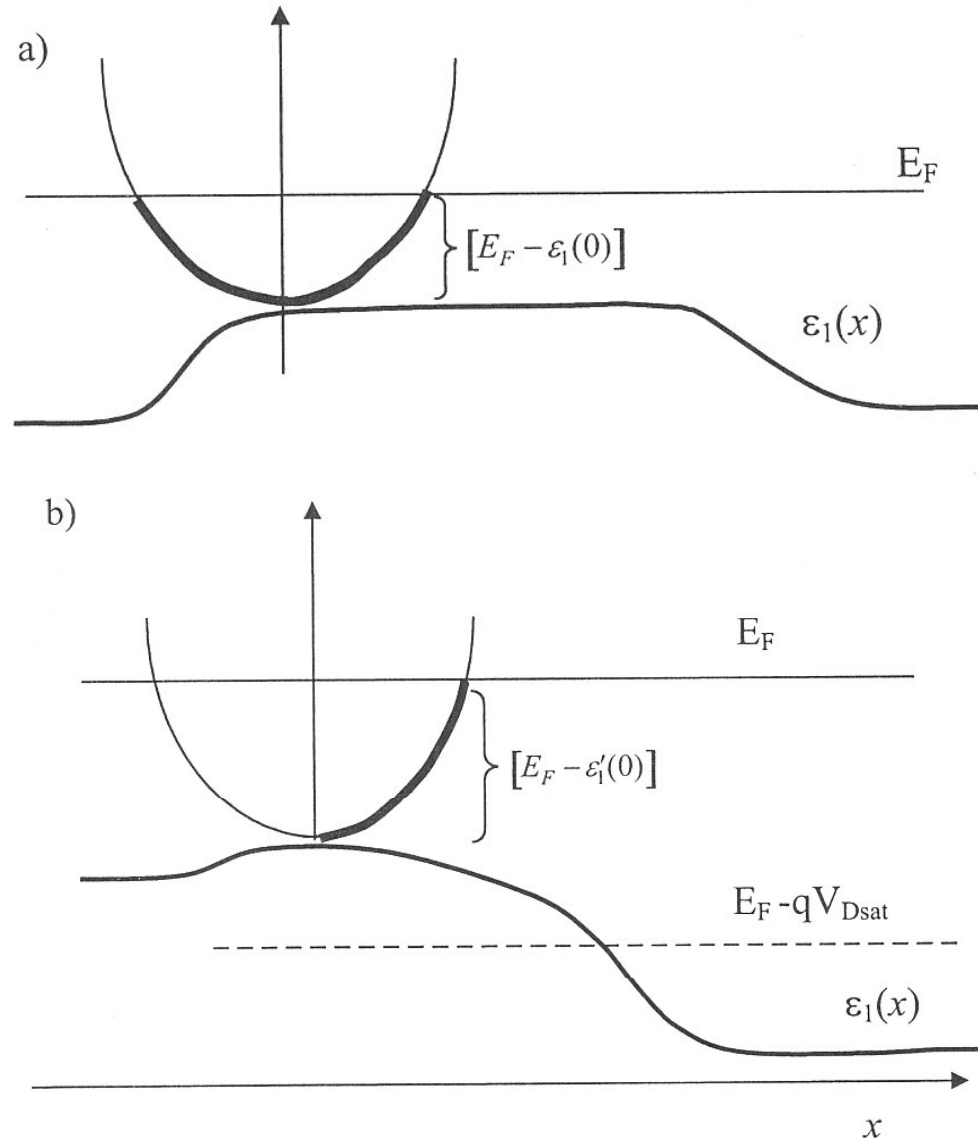
$$n_S^+(E_F) + n_S^-(E_F - qV_{DS}) = Q(0)/(-q) \approx C_{ox}(V_{GS} - V_T)/(-q)$$

- Current flow direction



At High Drain Bias

- At equilibrium
Equal amount of electrons move in both direction
- At high drain bias
Most electrons move in the positive direction



I-V Characteristic of Ballistic MOSFET

$$n_s^+(0) = \frac{N_{2D}}{2} \log\left(1 + e^{(E_F - \varepsilon_1)/k_B T_L}\right) = \frac{N_{2D}}{2} F_0(\eta_F)$$

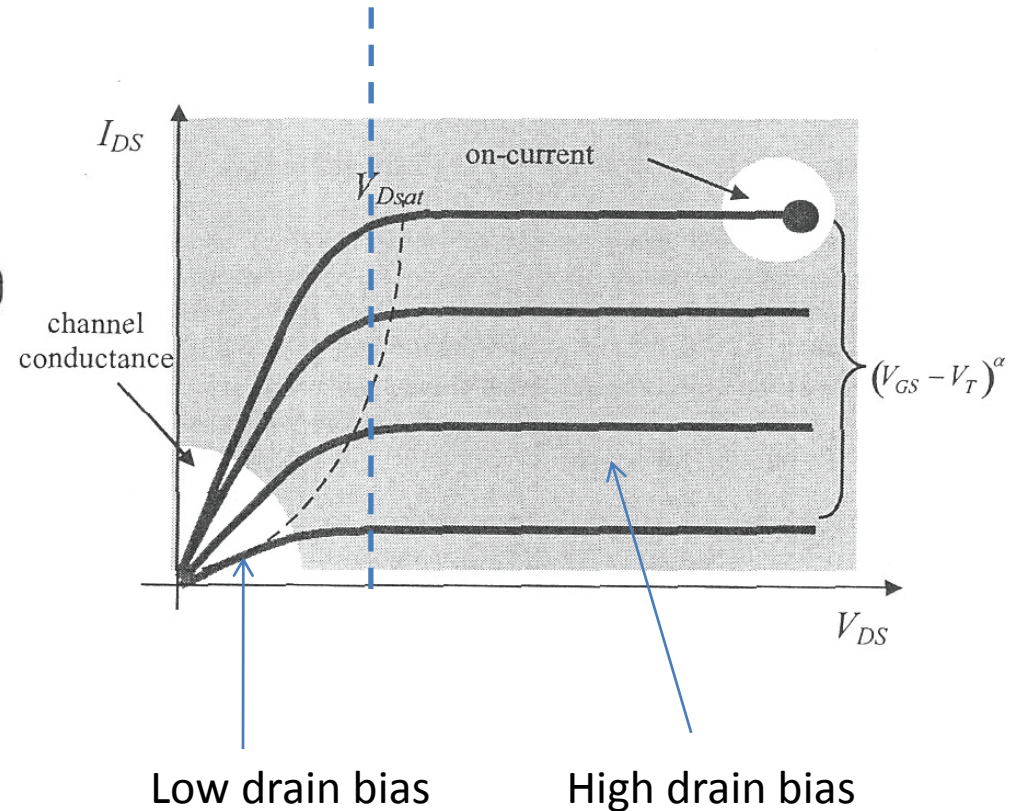
$$n_s^-(0) = \frac{N_{2D}}{2} \log\left(1 + e^{(E_F - qV_D - \varepsilon_1)/k_B T_L}\right) = \frac{N_{2D}}{2} F_0(\eta_F - U_D)$$

$$v^+ = v_T \frac{F_{1/2}(\eta_F)}{F_0(\eta_F)}$$

$$v^- = v_T \frac{F_{1/2}(\eta_F - U_D)}{F_0(\eta_F - U_D)}$$

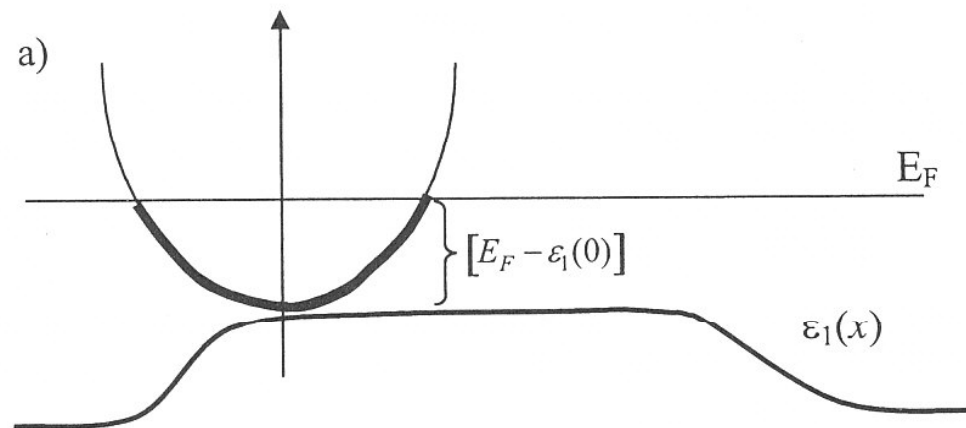
$$I^+ = qW n_s^+ v^+$$

$$I^- = qW n_s^- v^-,$$



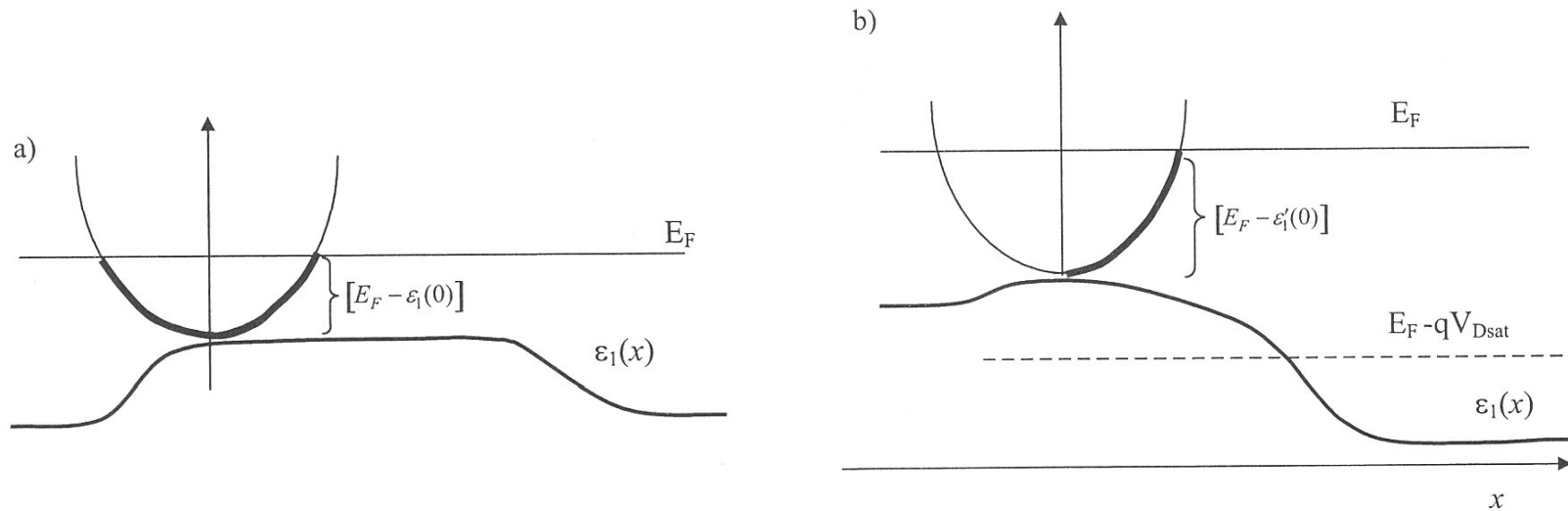
Fact 1 for Ballistic MOSFET

- Carrier distribution function at the barrier top consists of two thermal equilibrium halves, from Source and from Drain



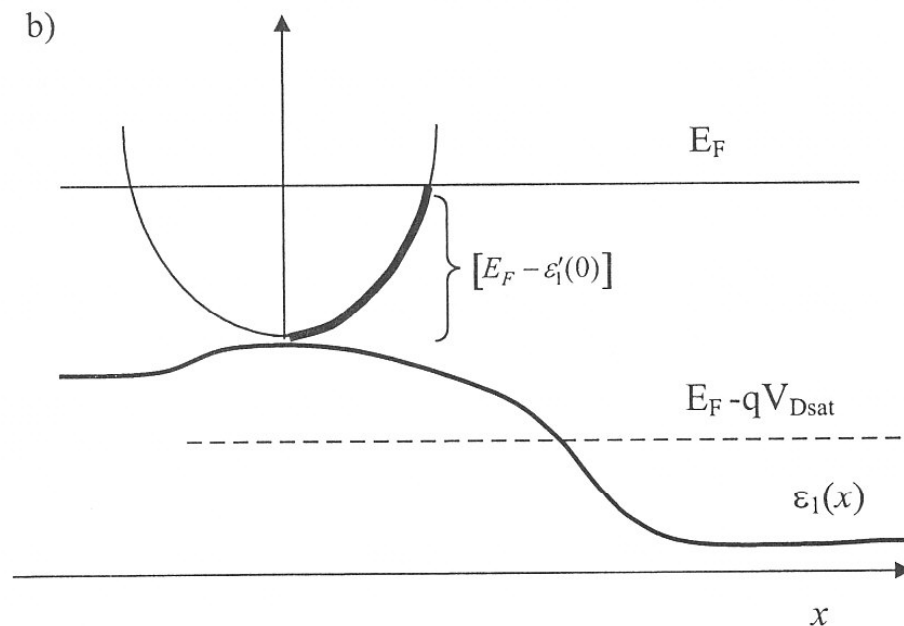
Fact 2 for Ballistic MOSFET

- The total carrier density at the barrier top is about a constant (for an electrostatically well-designed MOSFET)

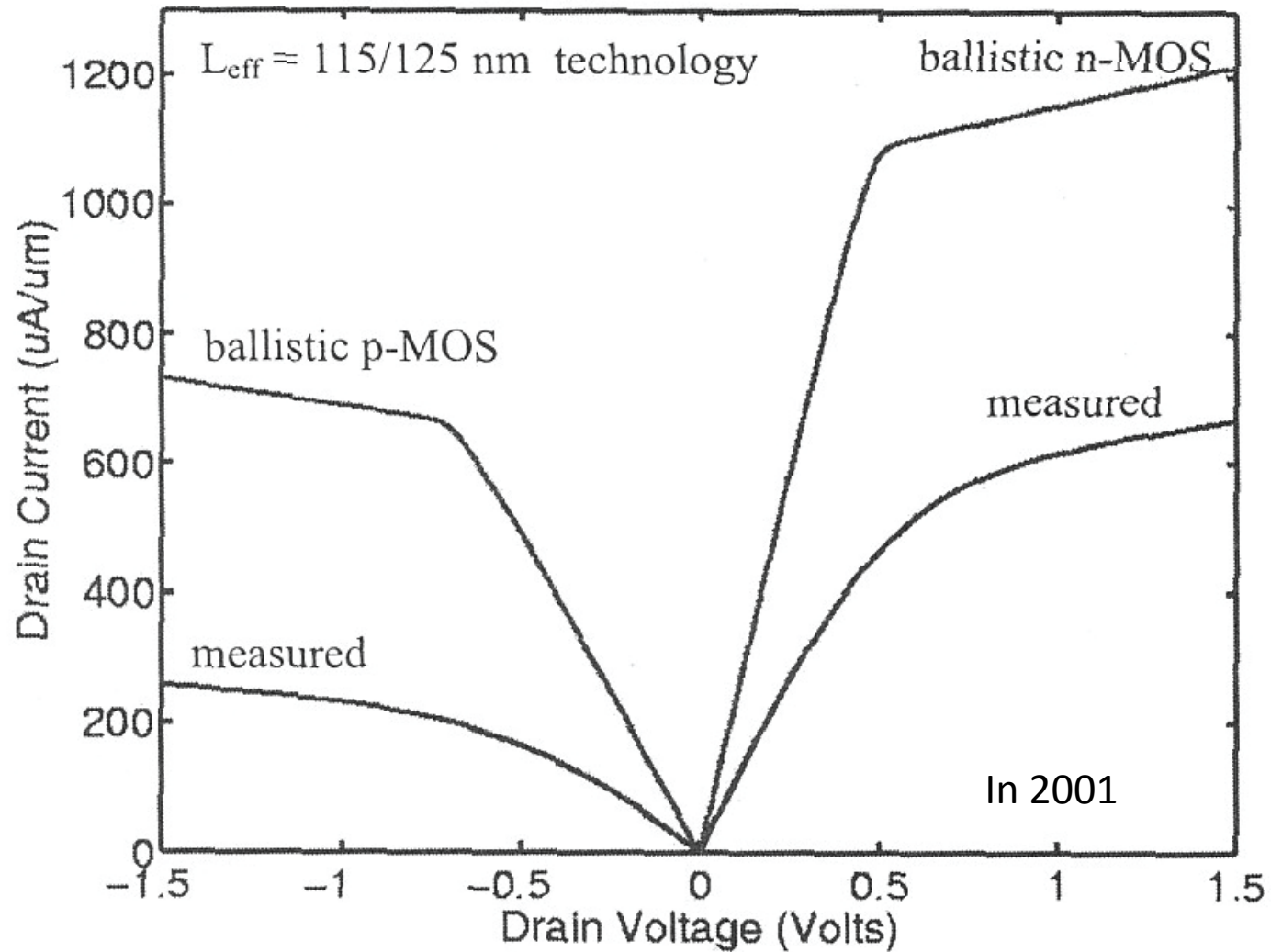


Fact 3 for Ballistic MOSFET

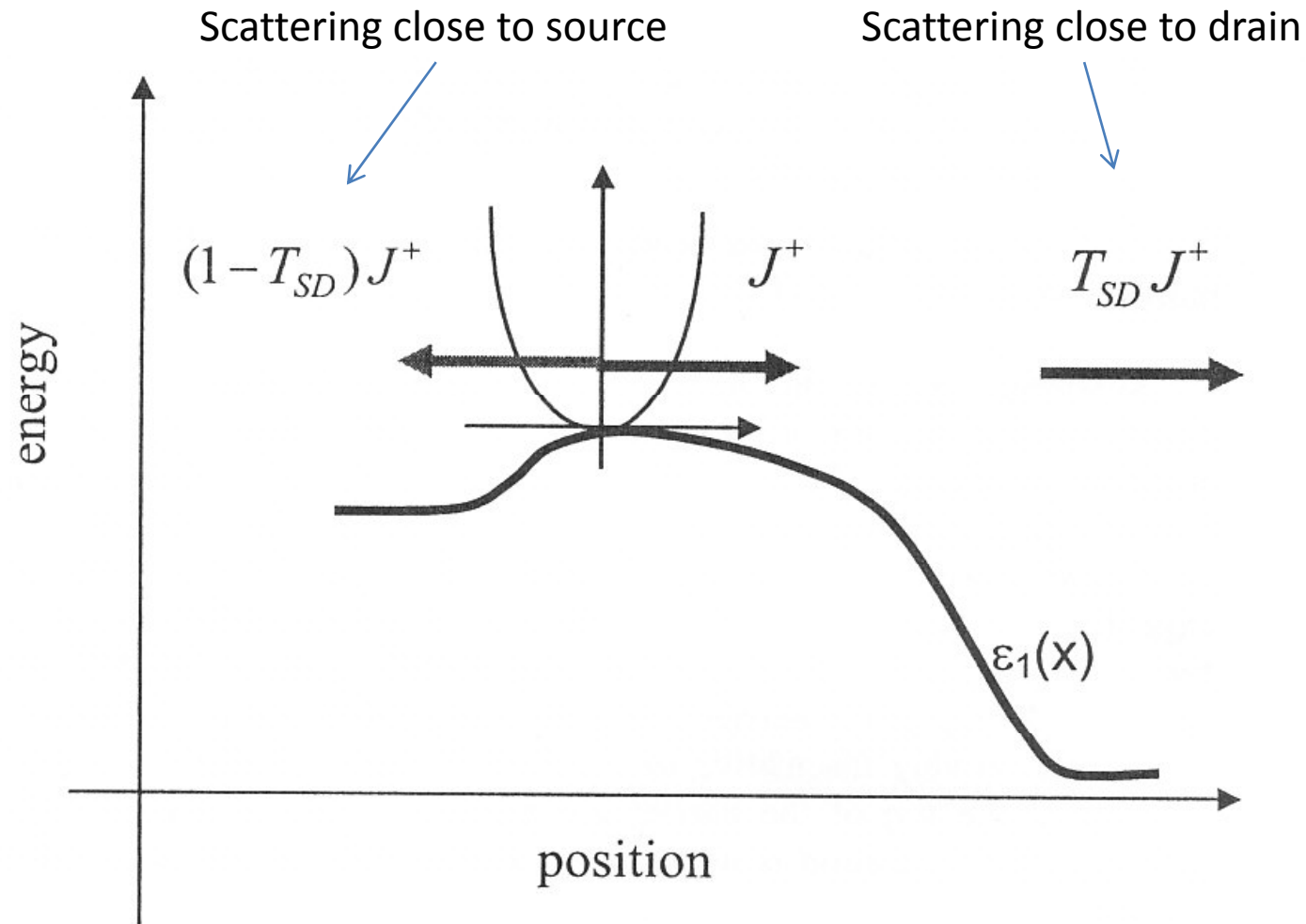
- The average velocity at the barrier top increases with V_{DS} and then saturates at a limit, which is the average velocity of a thermal equilibrium hemi-Fermi-Dirac distribution.
- The magnitude of saturated velocity increases with gate voltage.



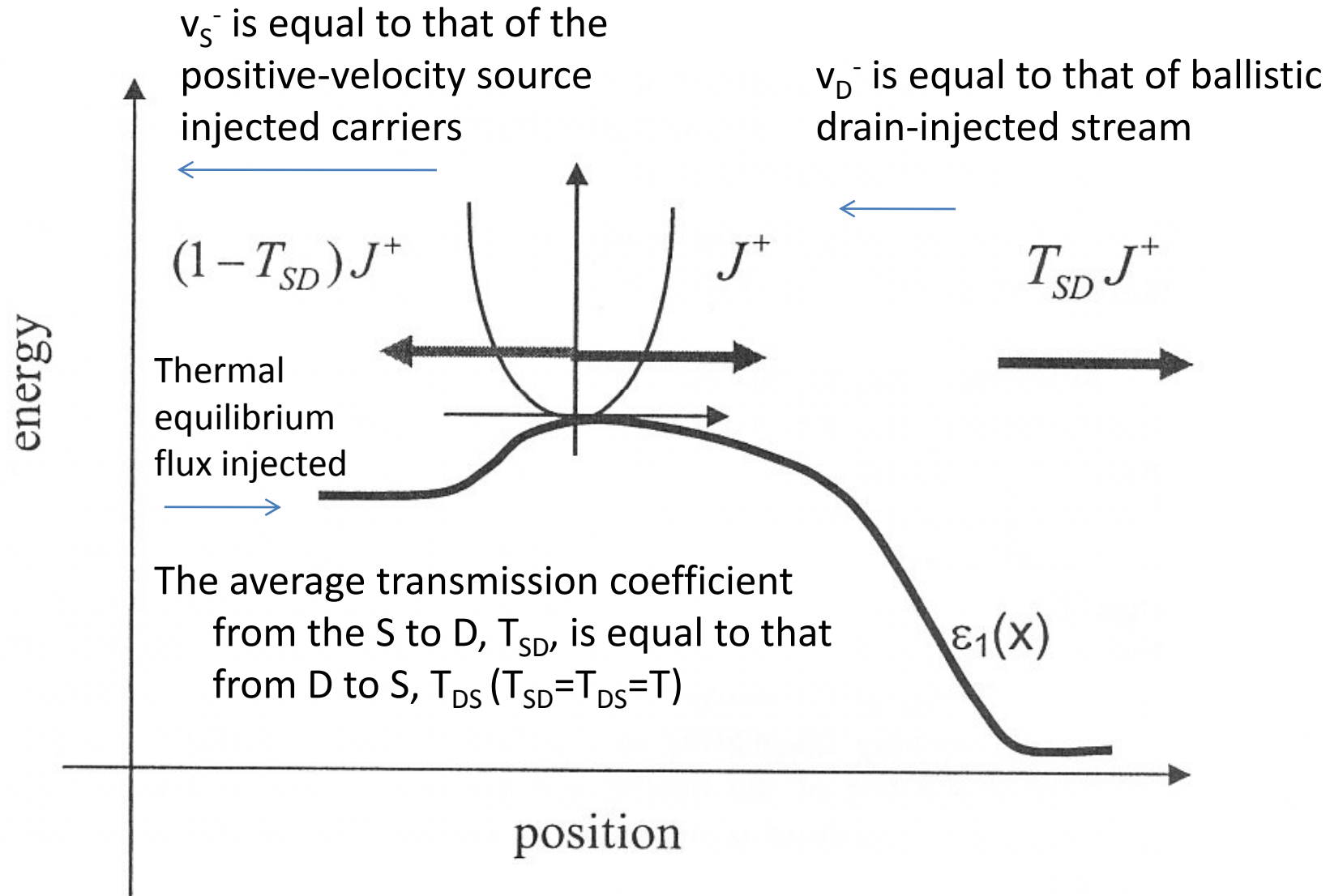
Classic vs. Ballistic MOSFET



Scattering is the Reason

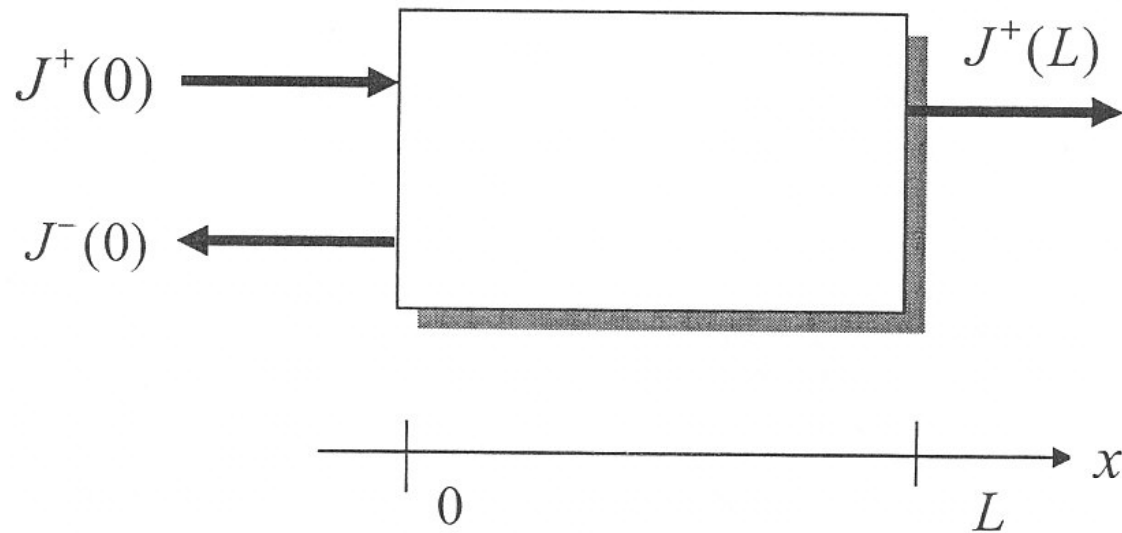


Assumptions

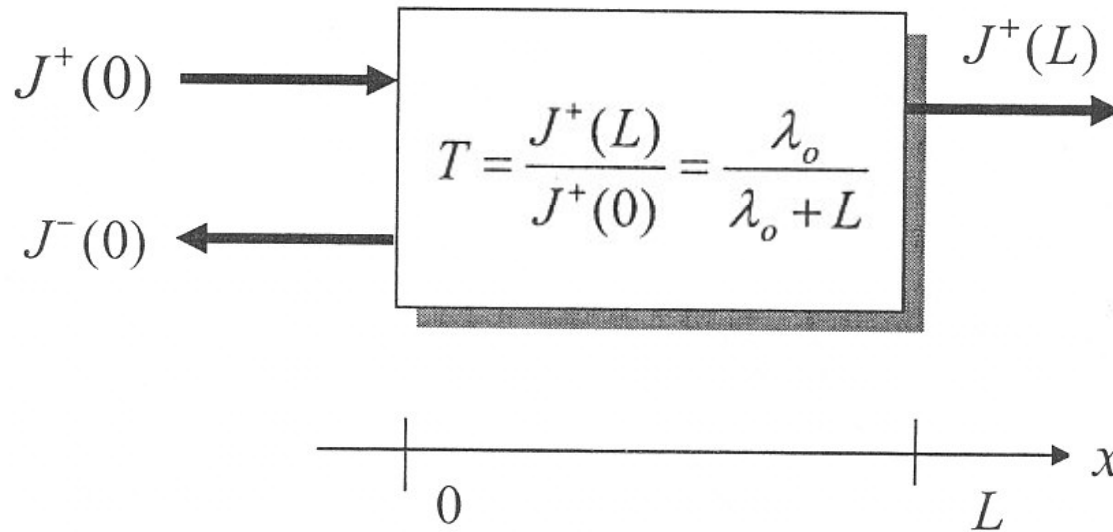


Low Drain Bias

- Channel length is the region length carriers diffuse. The potential drop across the channel is less than $k_B T_L / q \sim 26 \text{ mV}$ at RT



Near-Equilibrium Mean-free-path



Fick's law

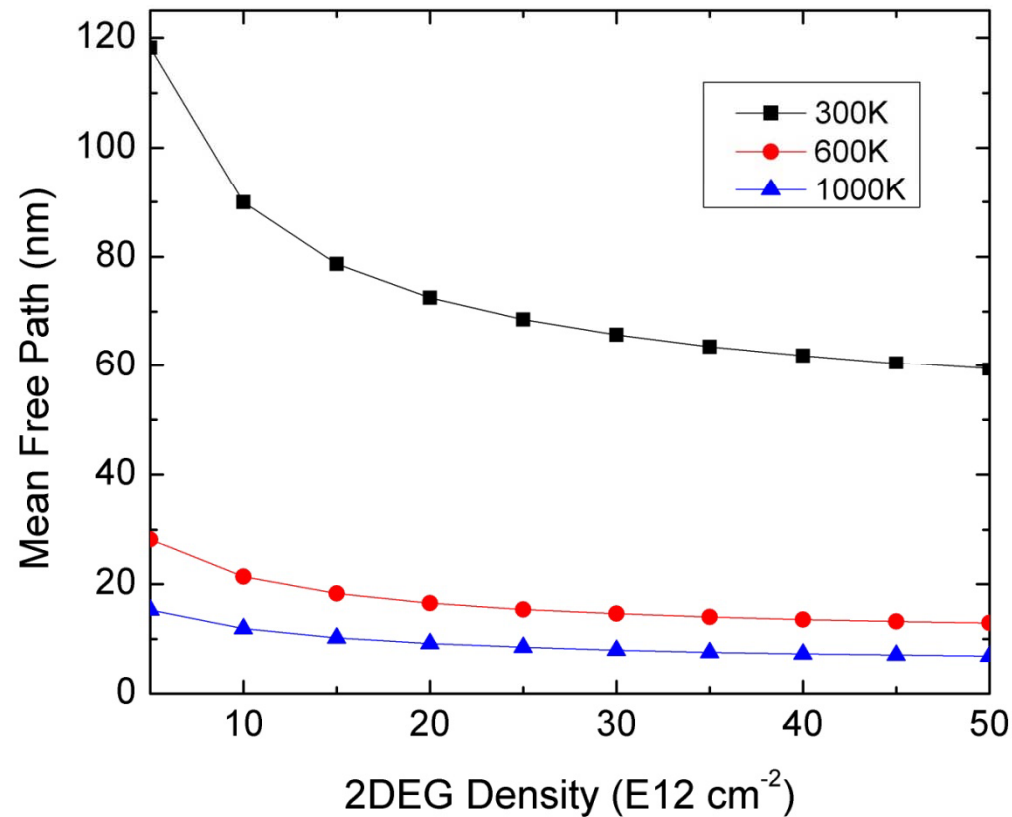
$$J = - \left(\frac{\lambda_o v_T}{2} \right) \frac{dn}{dx} = -D \frac{dn}{dx}$$

Apply Einstein relation

$$D \equiv \lambda_o v_T / 2 = (k_B T_L / q) \mu_{eff}$$

$$I_D = \left(\frac{W}{L + \lambda_o} \right) \mu_{eff} C_{ox} (V_G - V_T) V_D$$

Preliminary Calculation for GaN



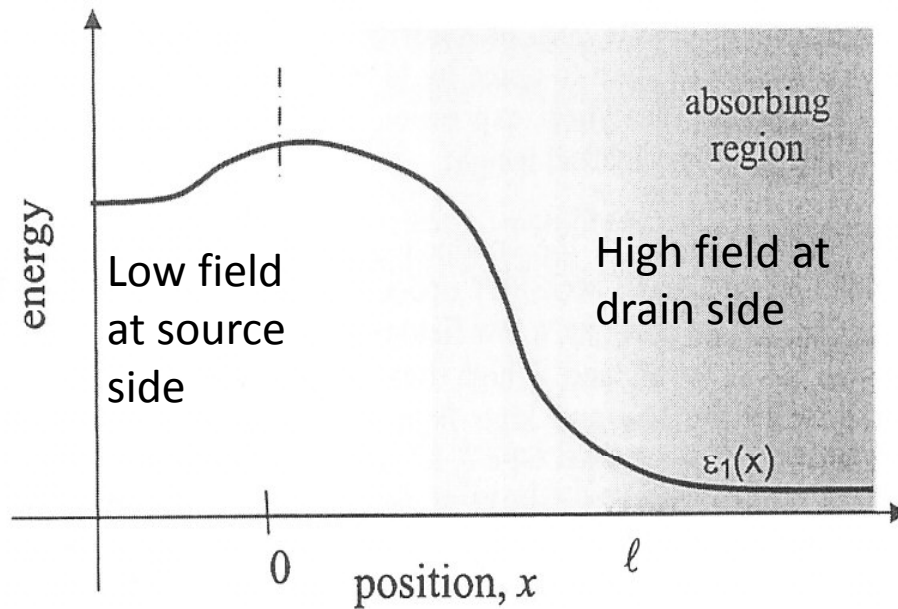
$$v_t = \sqrt{\frac{2k_B T_L}{\pi m^*}}$$

$$D \equiv \lambda_o v_T / 2 = (k_B T_L / q) \mu_{eff}$$

POP and AP scattering
considered

High Drain Bias

$$T = \frac{\lambda_0}{\lambda_0 + \ell}$$



$l=L$ for low drain bias

But only a portion of L for high drain bias (distance over which the first $k_B T_L / q$ of potential drops)

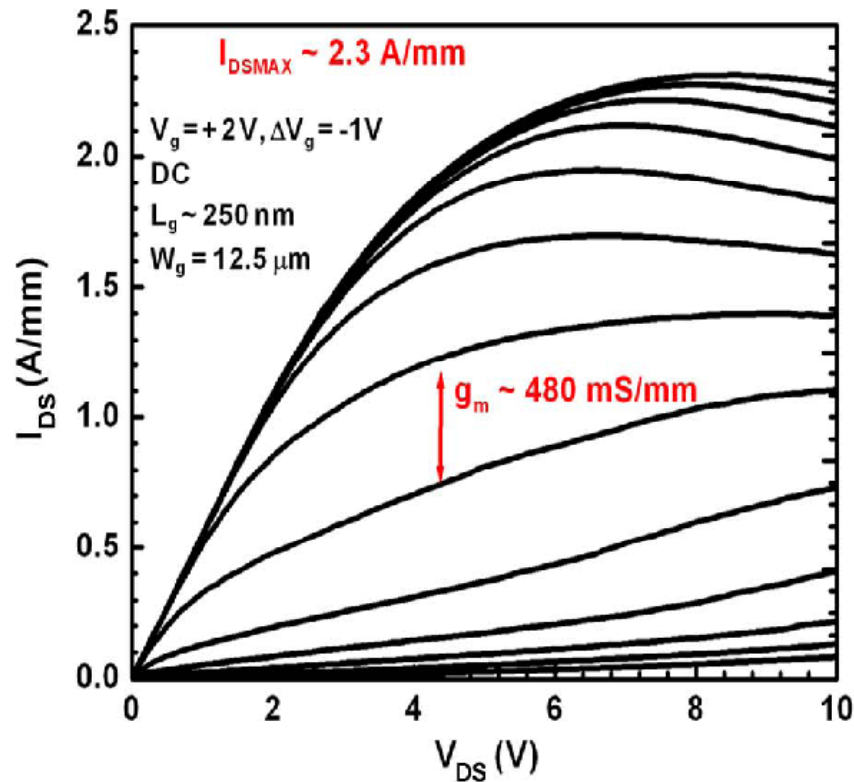
Beyond l , the carrier will be unlikely to return to the source after scattering

How Far Away from Ballistic

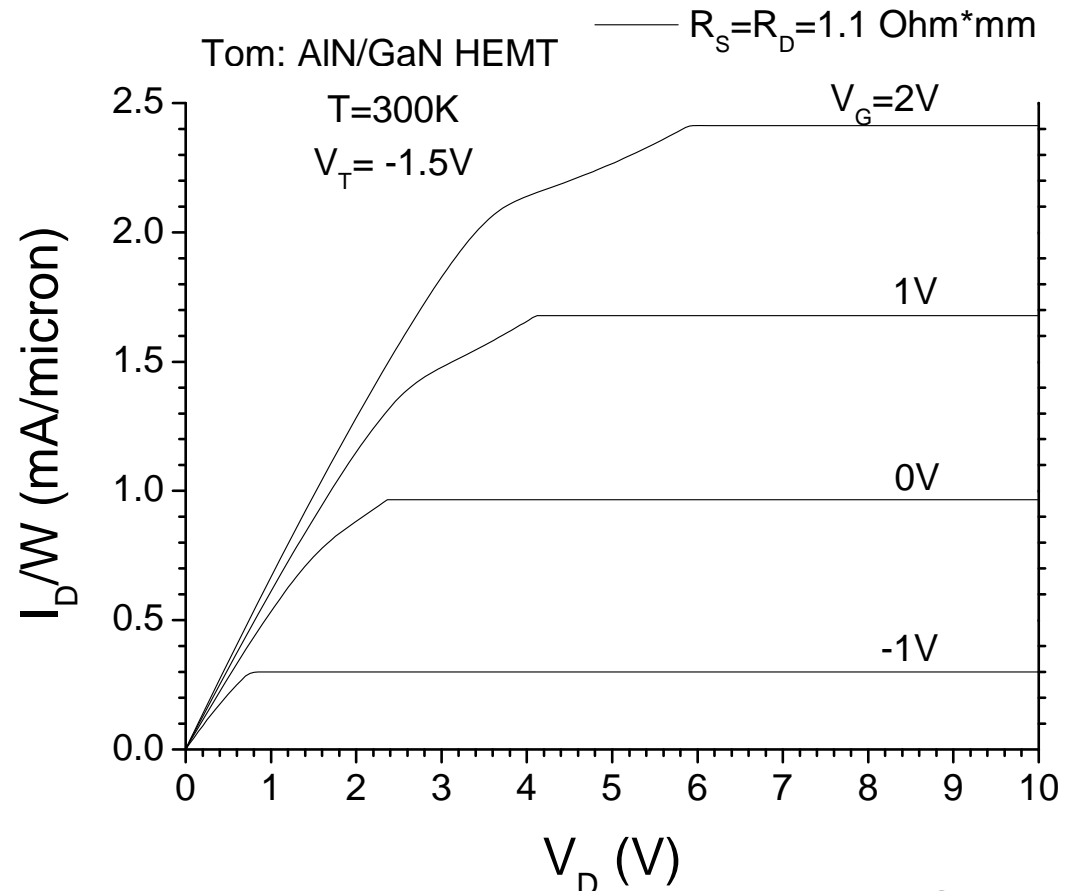
$$B = \frac{I_D(\text{on})}{I_D(\text{on-ballistic})} = \frac{T}{2-T} = \frac{\lambda_o}{2\ell + \lambda_o}$$

$$\lambda_o \gg 2\ell \longrightarrow B \rightarrow 1$$

This shows devices can operate relatively close to the ballistic limit even though they are several mean-free-path longer.



Device measured by Tom



Ballistic Model calculated by Guowang

Future Work

- Apply the model to GaN based HEMTs
- Include phonon scattering in GaN channel in the ballistic model
- Plot I-V for GaN based HEMT under ballistic or close to ballistic limit

THANK YOU!